

# Reduction of Intrinsic 1/f Device Noise in a CMOS Ring Oscillator

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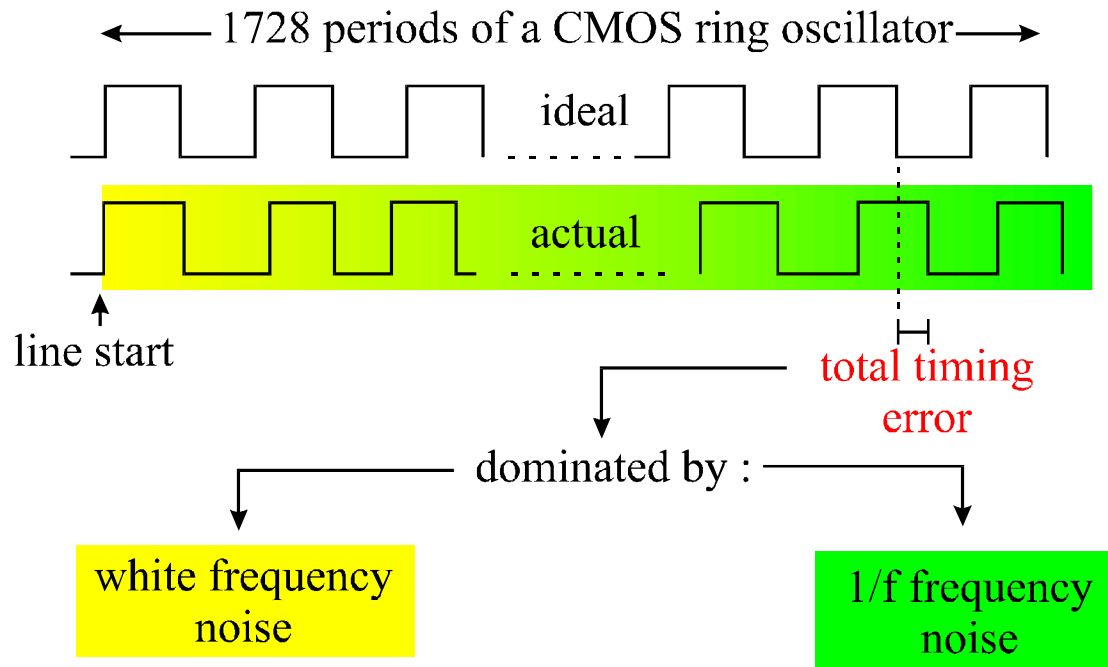
# Outline

- Introduction
- $1/f$  device noise under switched bias conditions  $\Rightarrow$  reduction !
- (How) does  $1/f$  noise reduction appear in a ring oscillator ?
- Ring oscillator phase noise measurements
- Conclusions



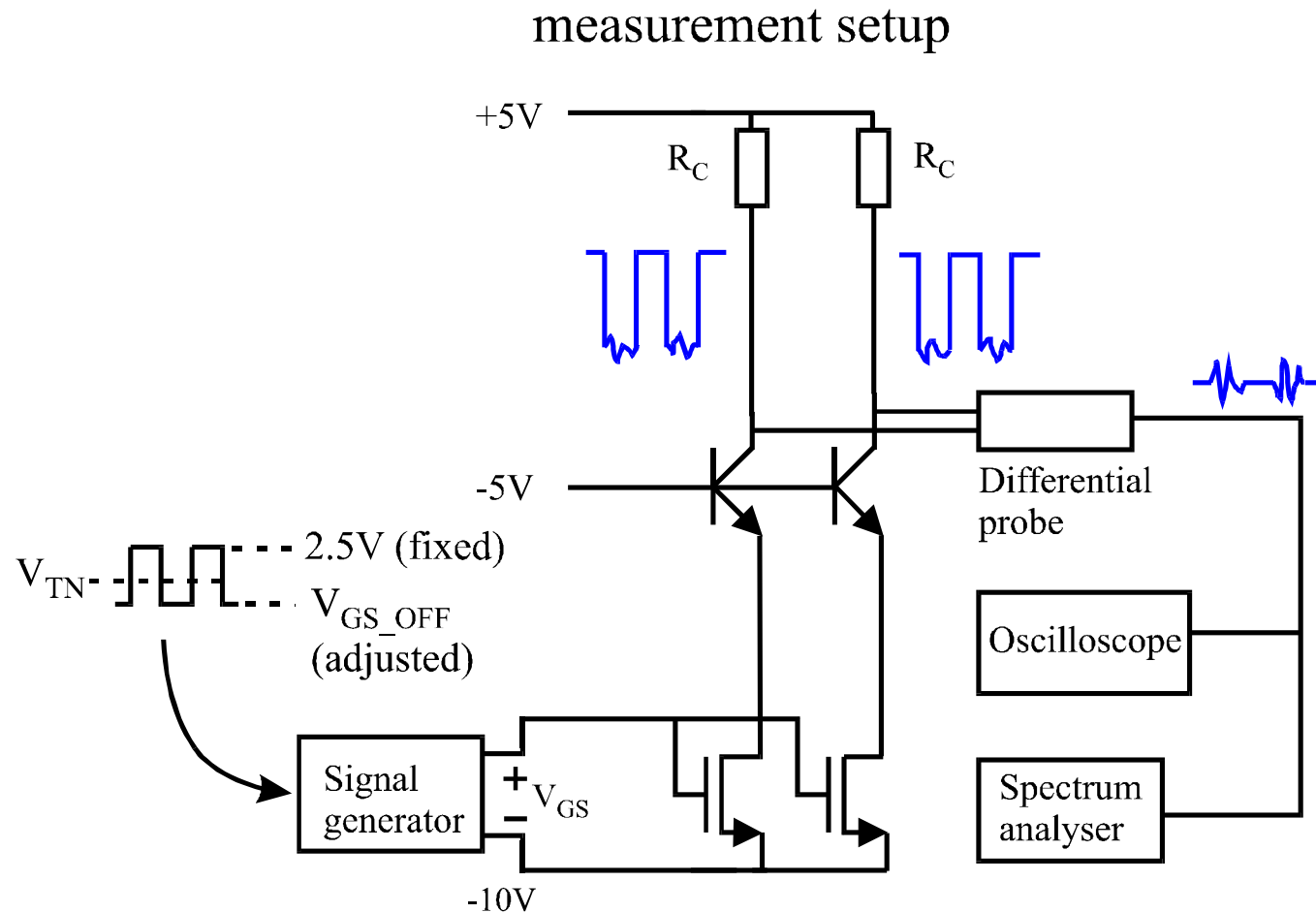
# Introduction

pixel clock generation  
in a  
100 Hz TV

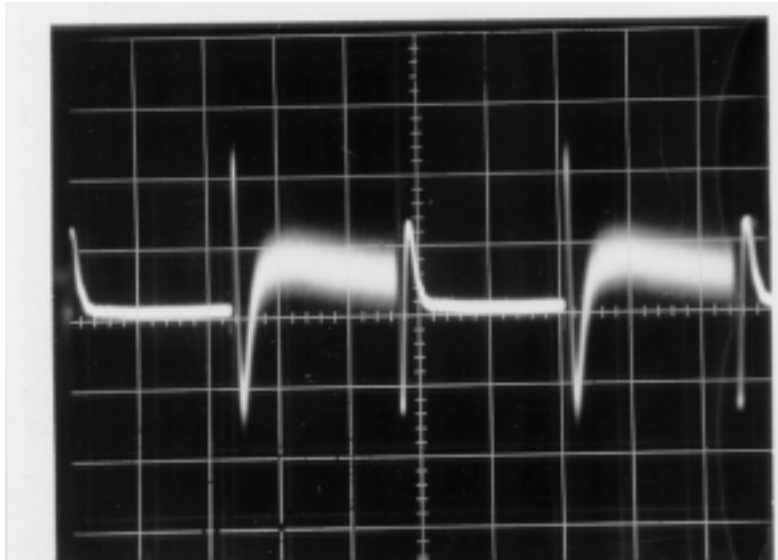


- Jitter measurements : lower 1/f frequency noise contribution than expected
- ⇒ **does the intrinsic MOS 1/f noise change due to periodical switching ?**
- ⇒ **(how) does this affect a ring oscillator's phase noise ?**

# 1/f device noise under switched bias conditions



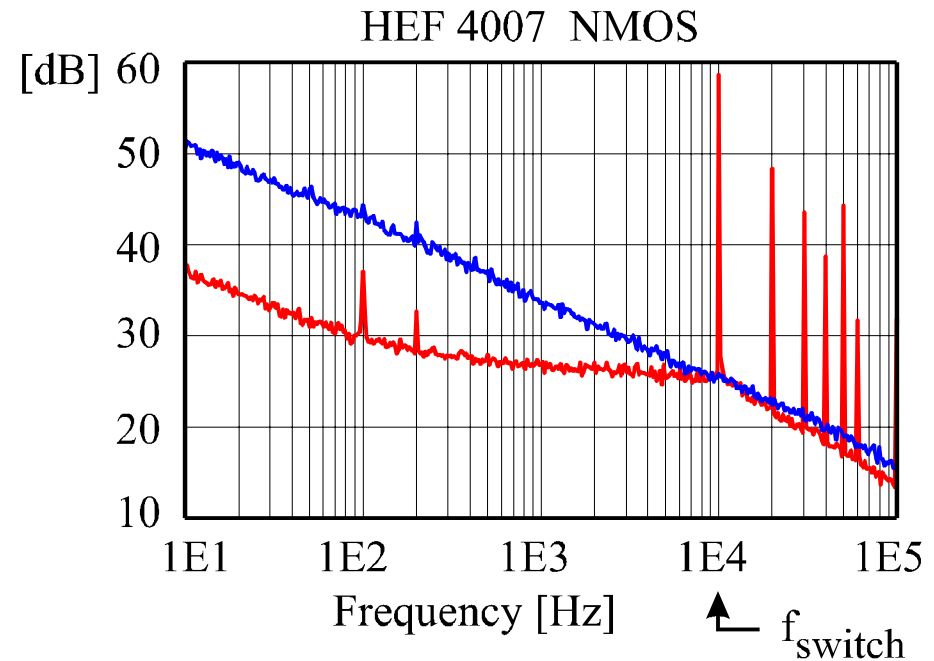
## Baseband measurement result



$\uparrow 2\text{mV/DIV} \rightarrow 20\mu\text{s/DIV}$

probe gain : 5x

$f_{\text{switch}} = 10\text{kHz}$



— not switched ,  $V_{\text{GS}} = 2.5\text{V}$

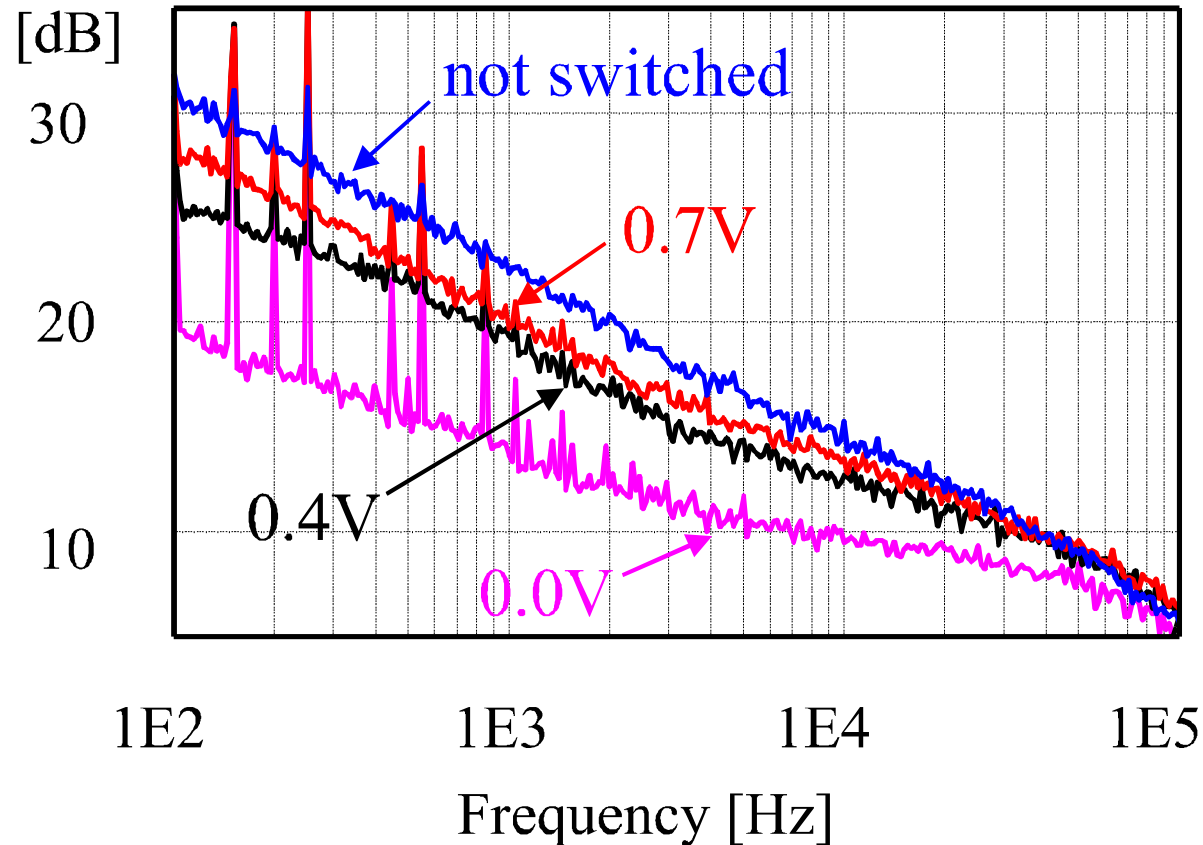
—  $V_{\text{GS\_ON}} = 2.5\text{V}$  ,  $V_{\text{GS\_OFF}} = 0\text{V}$   
Duty cycle = 50%

switching of MOS transistor  $\rightarrow$  reduction of *intrinsic*  $1/f$  device noise

[see also : Bloom & Nemirovsky , *Applied Physics Letters* 1991]



How does  $V_{GS\_OFF}$  affect the baseband 1/f noise spectrum ?



HEF 4007 NMOS

$V_{GS\_ON} = 2.5V$

$V_T = 1.5V$

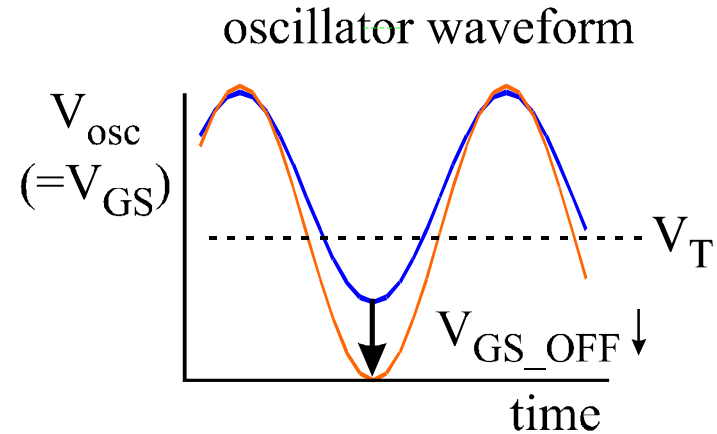
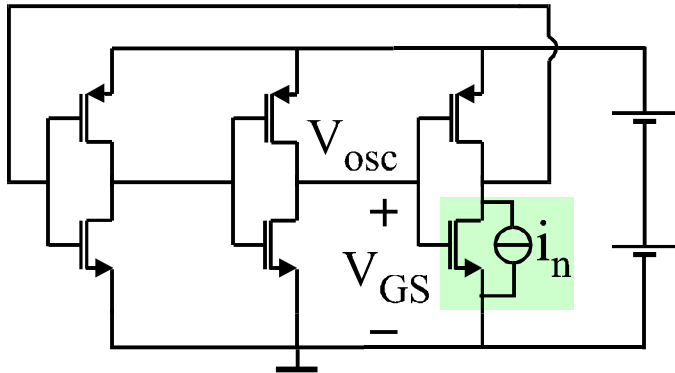
$f_{switch} = 2MHz$

Duty cycle = 50%

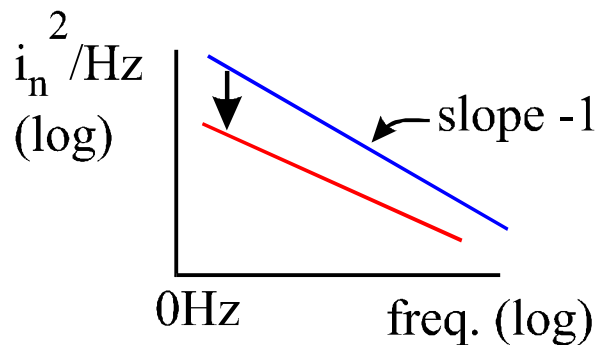
$V_{GS\_OFF} \downarrow \Rightarrow$  intrinsic MOS 1/f noise  $\downarrow$



# (How) does 1/f noise reduction appear in a ring oscillator ?

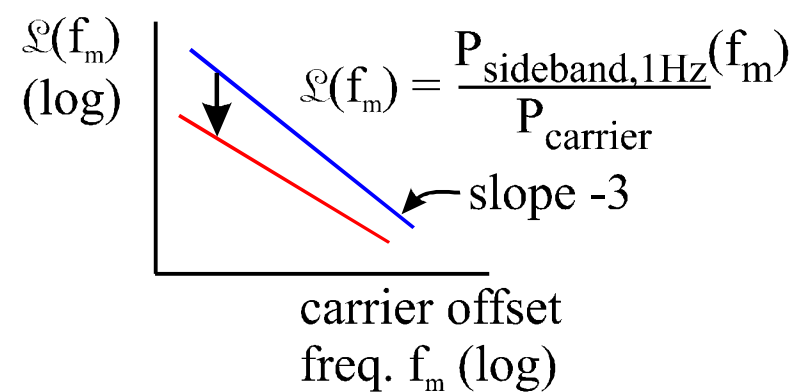


baseband 1/f noise spectrum

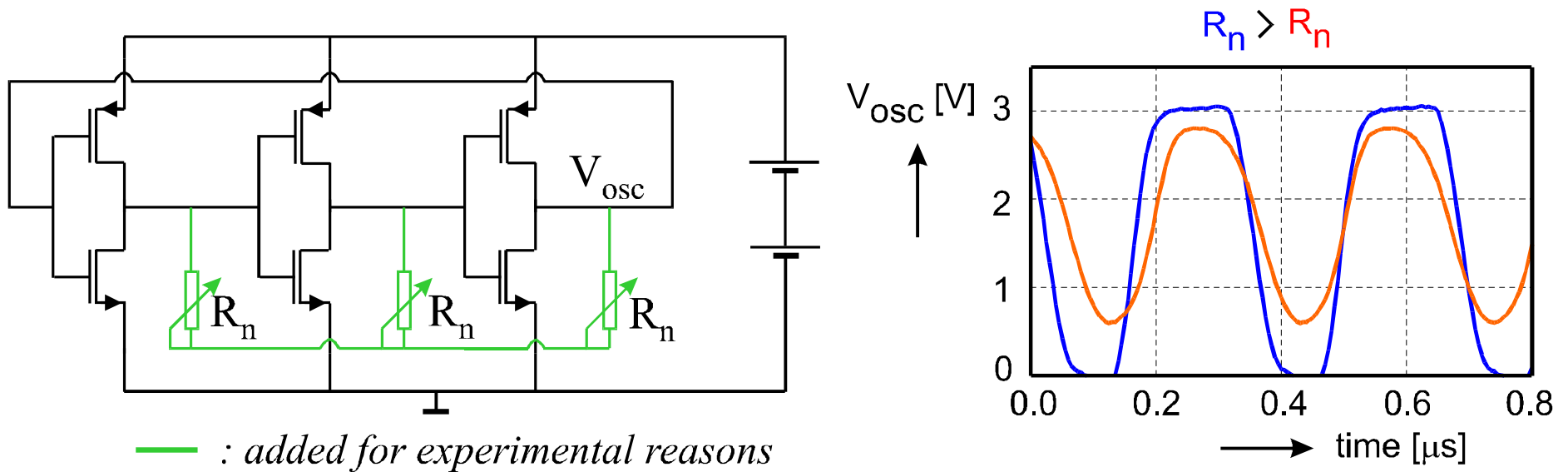


*upconversion*  
(freq. modulation)

relative sideband strength



How to vary the  $V_{GS\_OFF}$  of the transistors easily ?



$R_n \uparrow \Rightarrow$ 

- $V_{GS\_OFF} \downarrow$
- $f_{osc}$  hardly changes

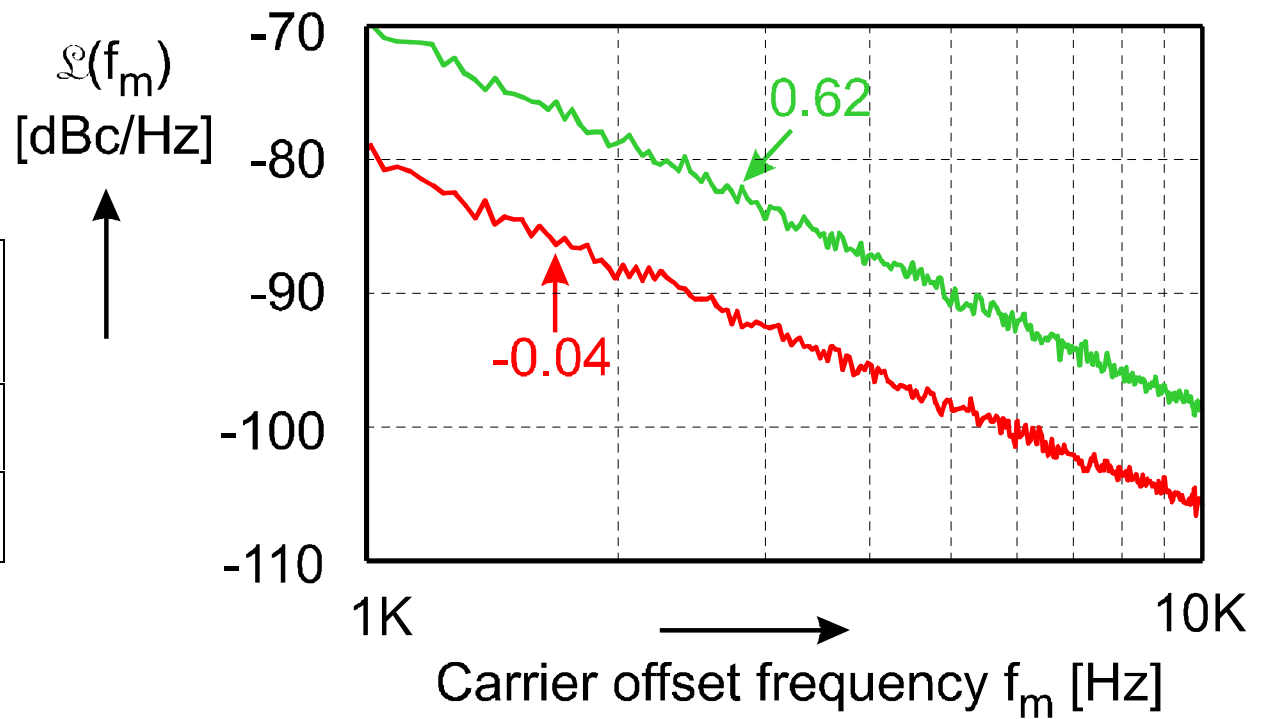
 $\Rightarrow$   **$1/f$  noise induced phase noise  $\downarrow$  ?**



# Phase noise measurement results (1)

$V_{DD} = 3V$

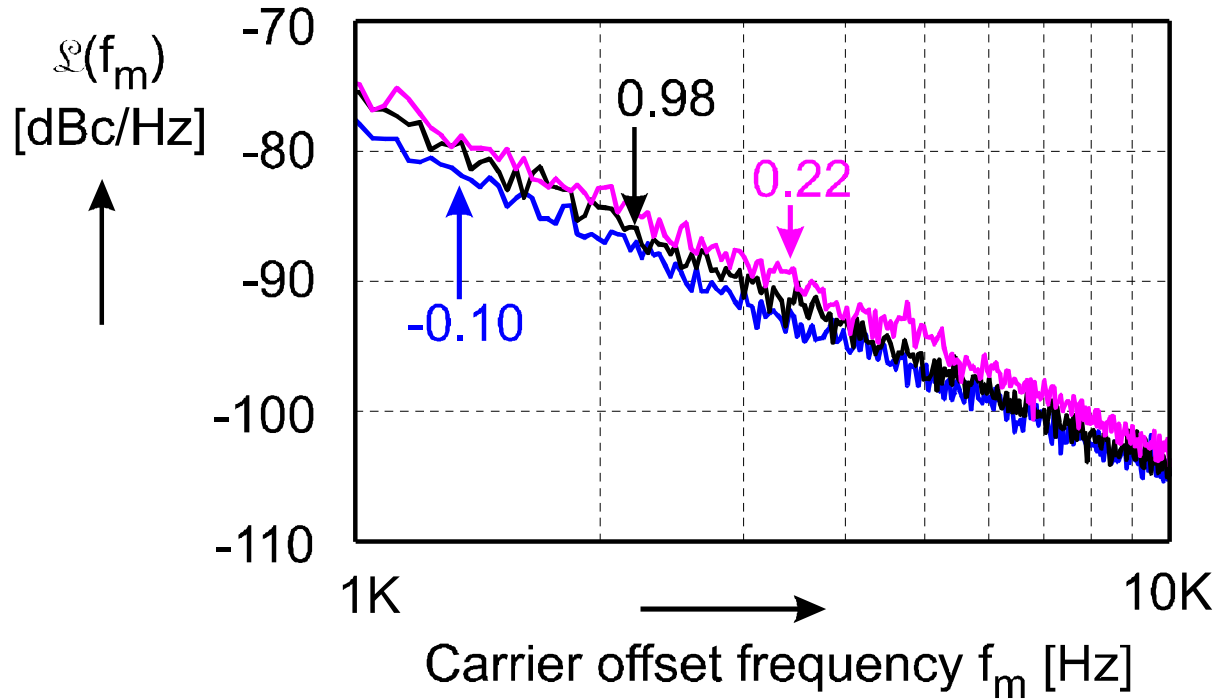
$F_{osc}$ [MHz]	$V_{MAX}$ [V]	$V_{MIN}$ [V]
3.016	3.1	-0.04
3.274	2.8	0.62



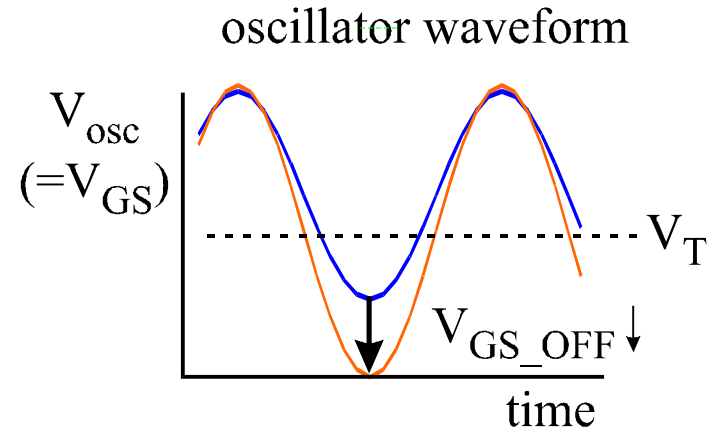
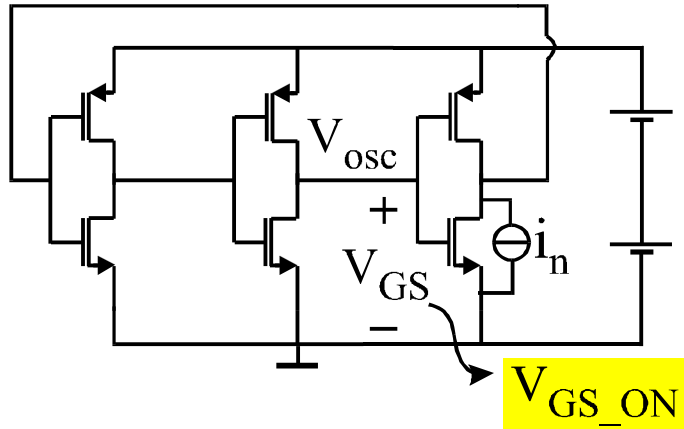
# Phase noise measurement results (2)

$V_{DD} = 4.5V$

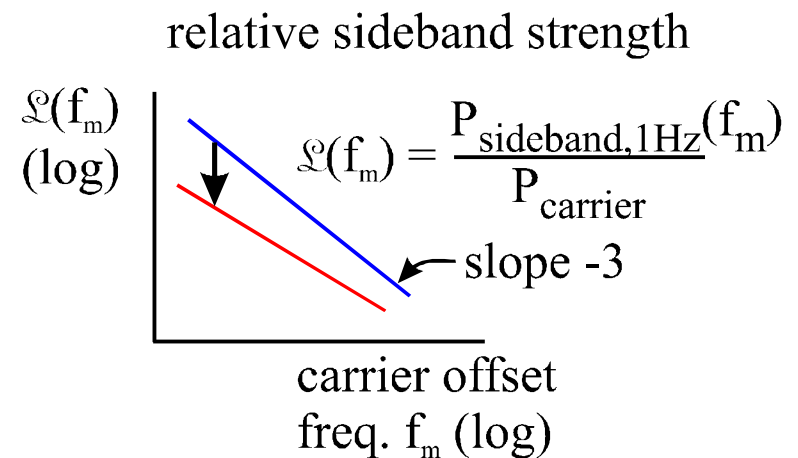
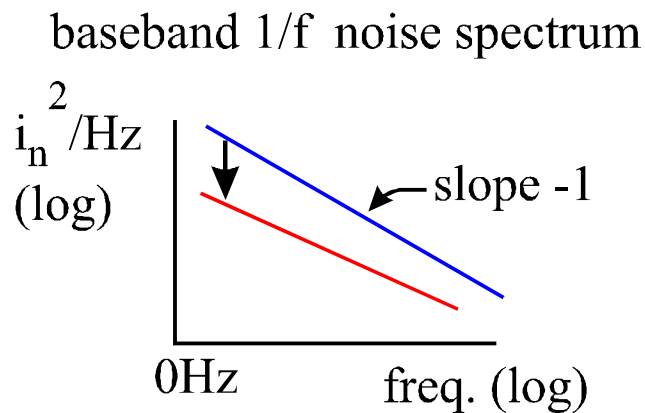
$F_{osc}$ [MHz]	$V_{MAX}$ [V]	$V_{MIN}$ [V]
6.17	4.5	-0.10
7.03	4.2	0.22
7.94	3.9	0.98



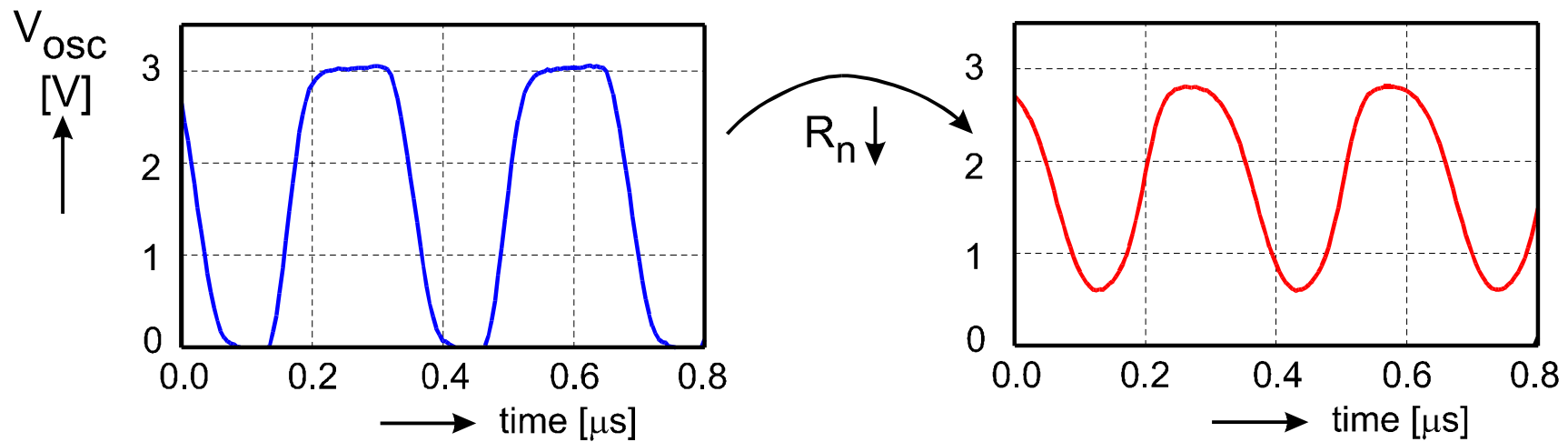
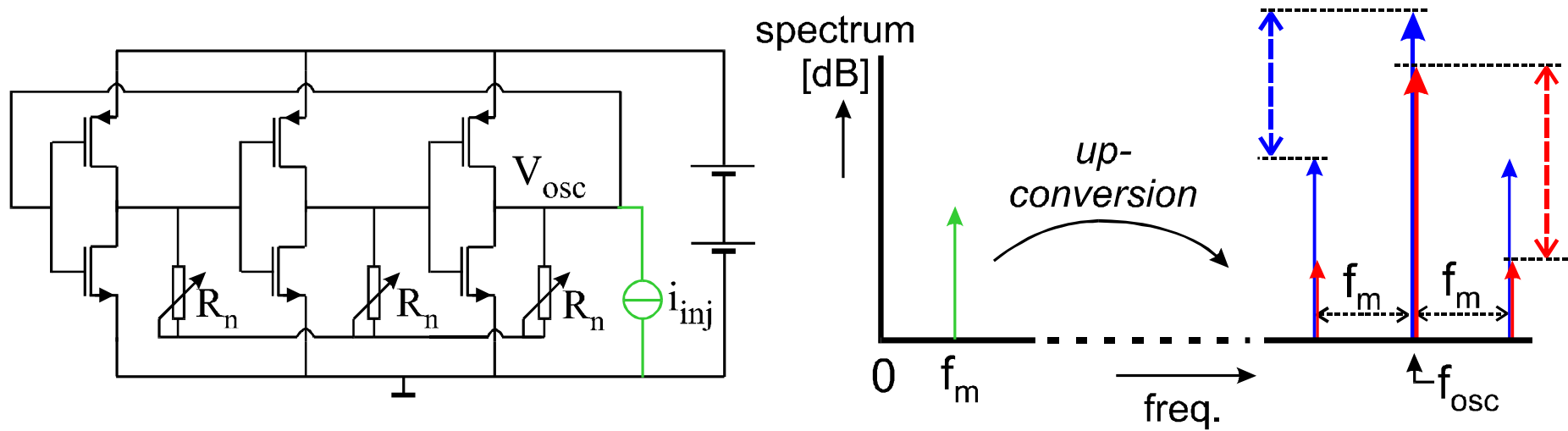
# Corrections are needed



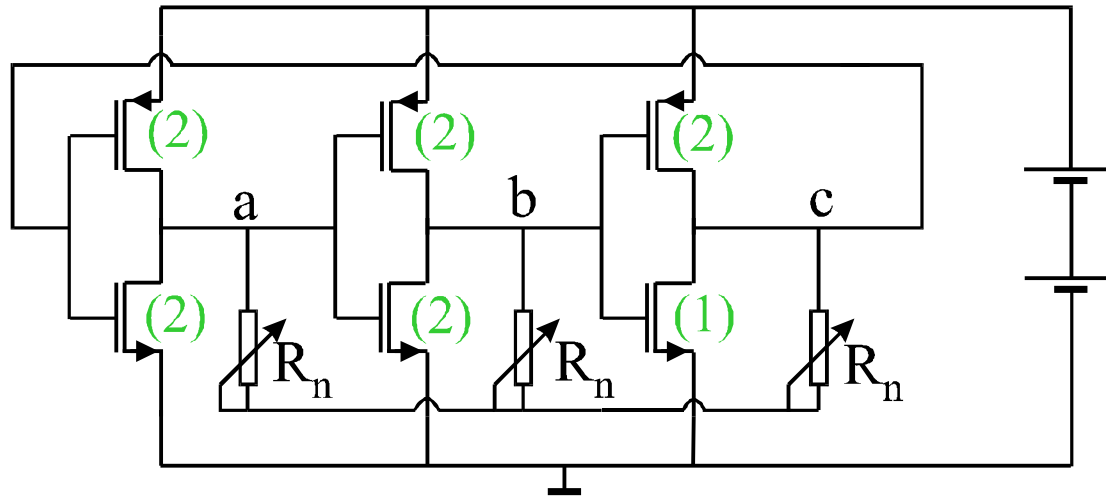
upconversion  
(freq. modulation)



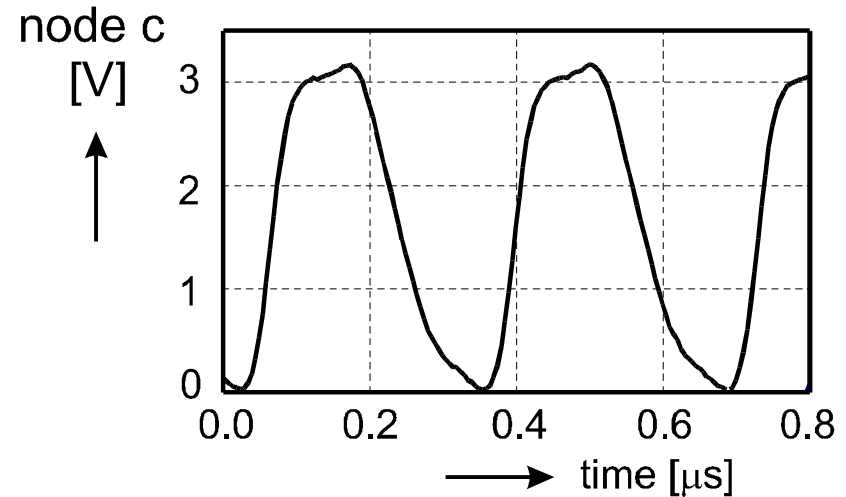
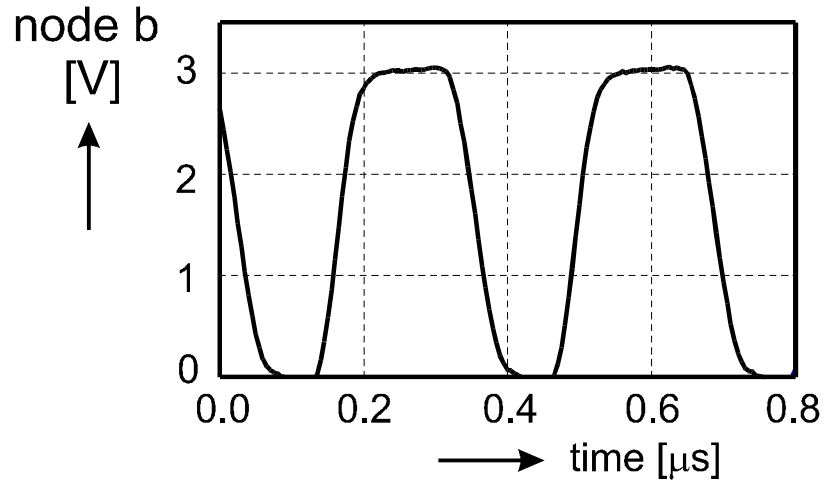
# Correction for changes in upconversion



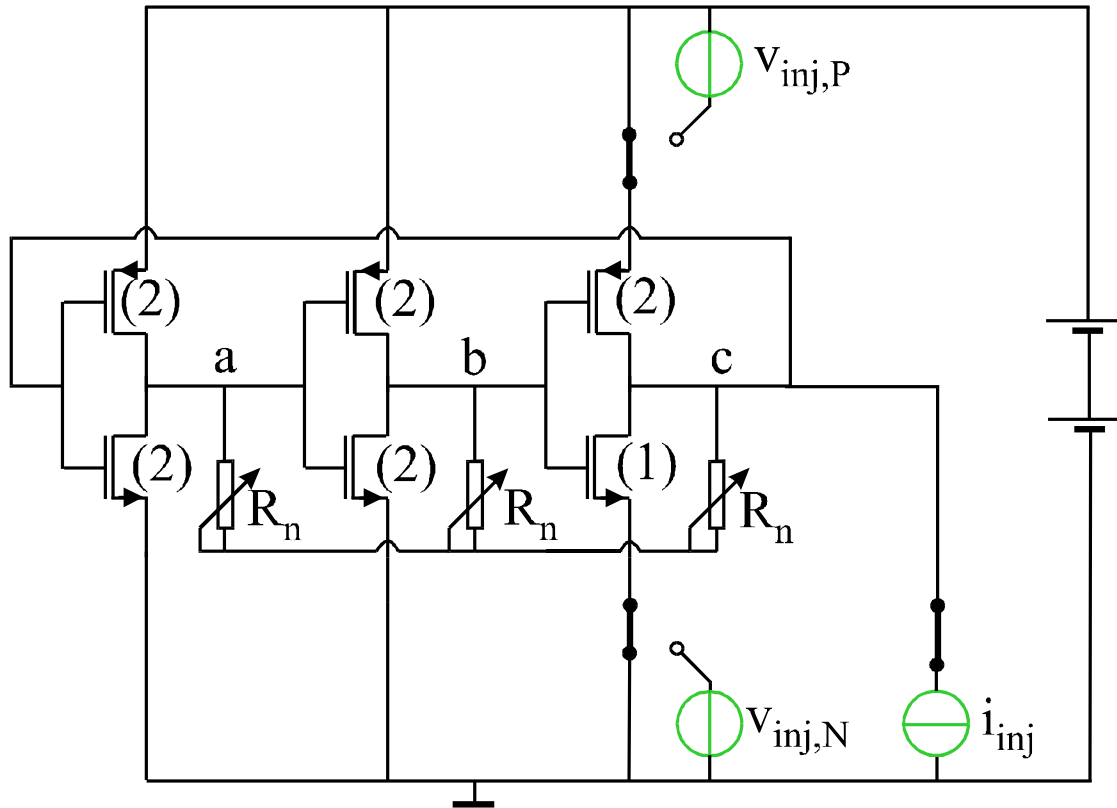
# Measurement of upconversion (1)



Due to asymmetry of waveform, node c will dominate upconversion  
*[Hajimiri JSSC feb. 1998]*



## Measurement of upconversion (2)



Example :

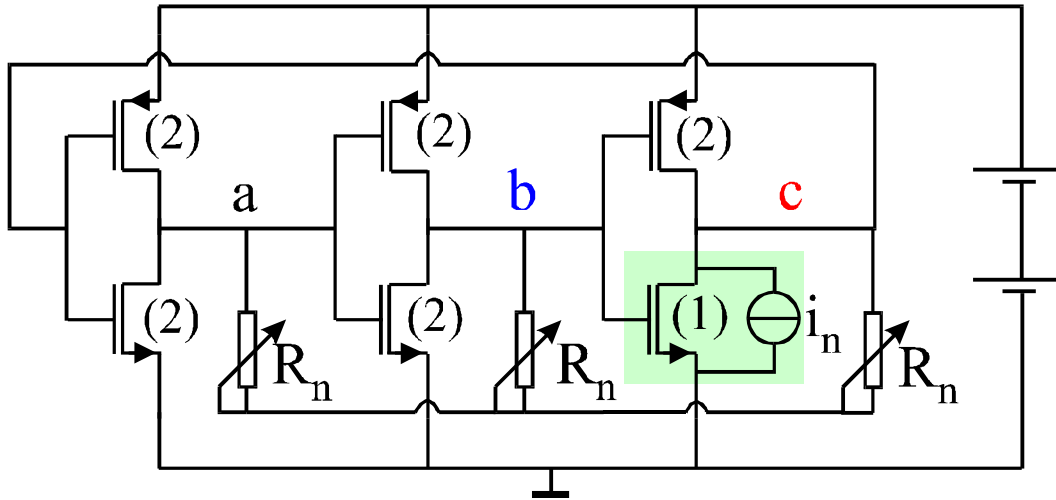
$i_{inj} : 1\mu A @ 10 \text{ kHz}$

injection at node :	upconversion [dB]
a	- 52.96
b	- 69.63
<b>c</b>	<b>- 39.67</b>

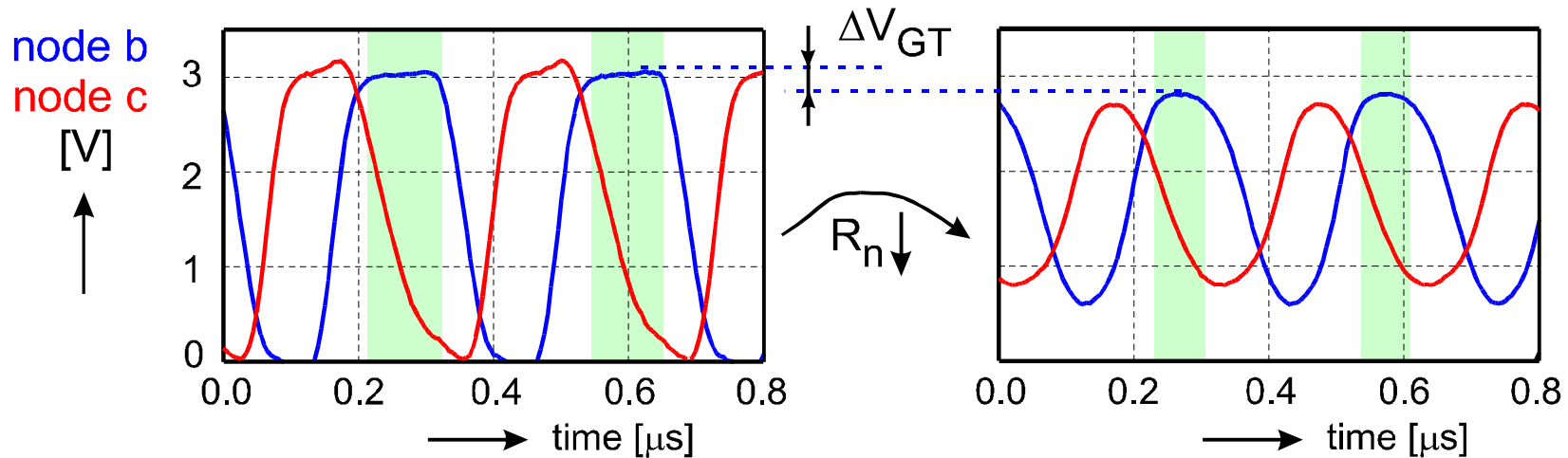
$V_{inj} : 0.3\text{mV} @ 10 \text{ kHz}$

injection at source :	upconversion [dB]
<b>NMOS</b>	<b>- 39.92</b>
PMOS	- 49.13

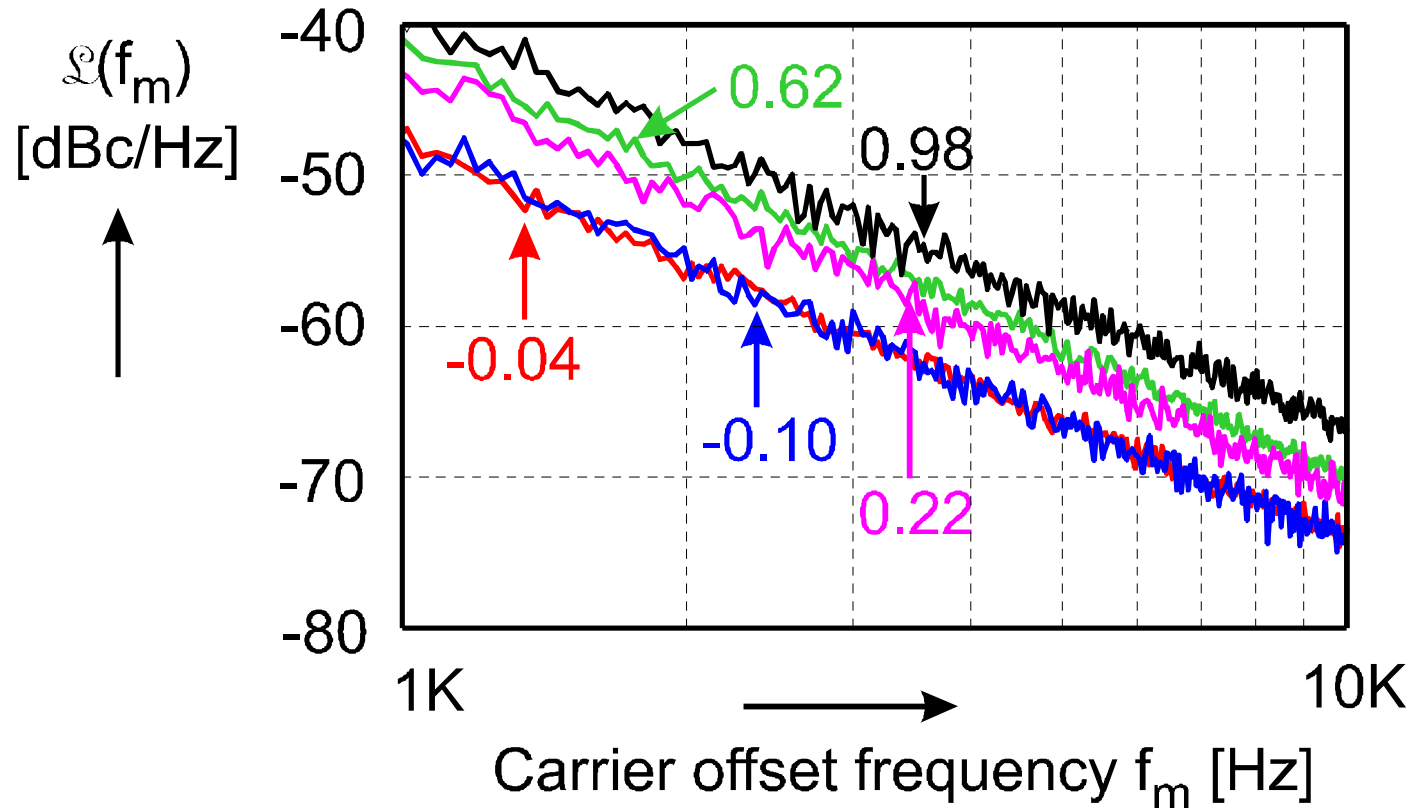
# Correction for changes in $V_{GS\_ON}$



$$\frac{i_n^2}{\Delta f} = \frac{K_{fl} \cdot g_m^2}{C_{ox} \cdot W \cdot L \cdot f} \sim (V_{GT})^2$$



# Phase noise measurement results after correction



$V_{GS\_OFF} \downarrow \Rightarrow 1/f$  noise induced phase noise  $\downarrow$





# Conclusions

- phase noise measurements of a CMOS ring oscillator can be related to baseband 1/f device noise measurements :

$$\begin{aligned} V_{GS\_OFF} \downarrow &\Rightarrow 1/f \text{ device noise } \downarrow \\ &\Rightarrow 1/f \text{ noise induced phase noise } \downarrow \end{aligned} \quad (\textit{design criterium})$$

- upconversion should be taken into account

